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*Japan 2014*



# 3D ICs: Recent Advances in the Industry

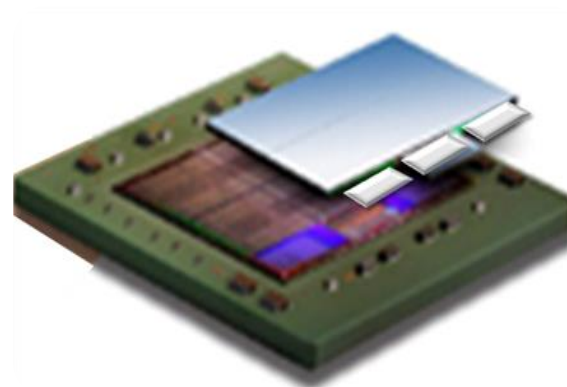
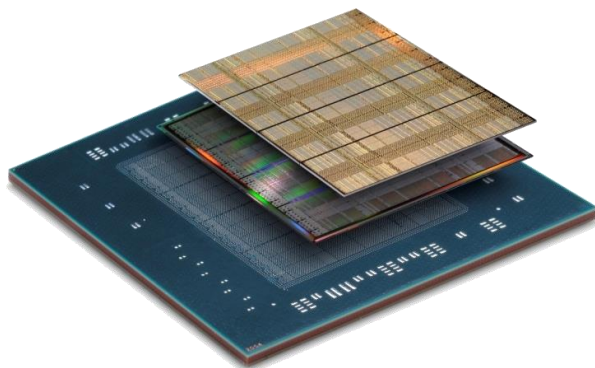
Suresh Ramalingam

Senior Director, Advanced Packaging



# Outline

- 3D IC Background
- 3D IC Technology Development
- Summary
- Acknowledgements



**Stacked Silicon Interconnect Technology** Refers to Xilinx 3D solutions

# 3D IC Background



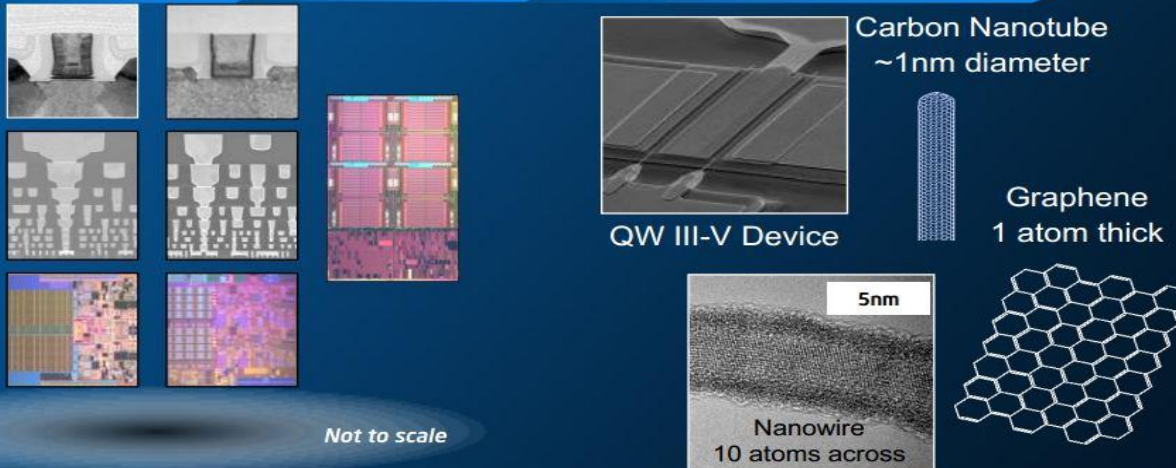
# Technical Challenges & Costs Are Growing

Our visibility always ~10 yrs – need broad exploration

## TECHNOLOGY GENERATION

45nm 2007    32nm 2009    22nm 2011    14nm 2013    10nm 2015    7nm 2017    Beyond 2020

MANUFACTURING    DEVELOPMENT    RESEARCH



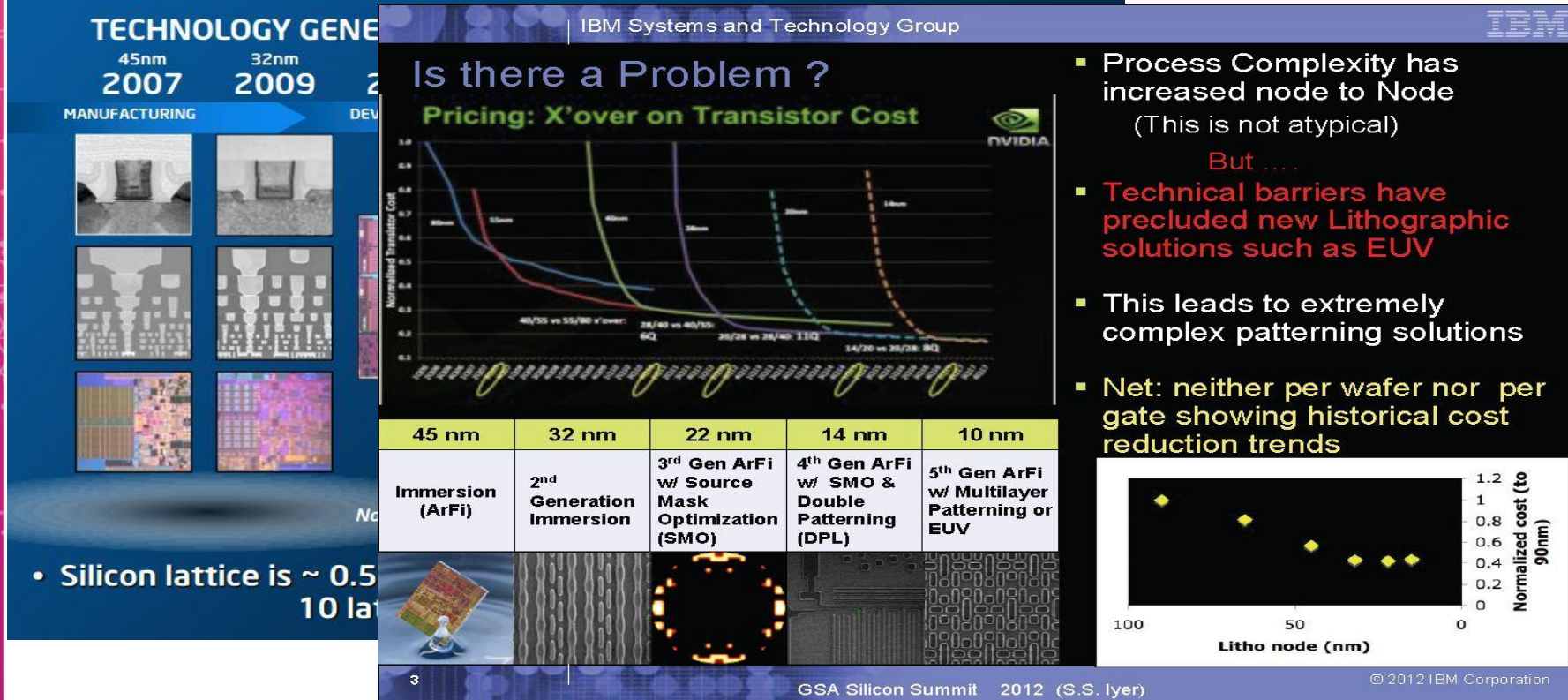
- Silicon lattice is ~ 0.5nm, hard to imagine good devices smaller than 10 lattices across – reached in 2020



- Process Technology Path Below 7nm is unclear
- Cost Reduction Slowing from Complexity / Investment Increases
- Cost Per Wafer & Cost Per Gate Deviating from Historical Reduction

# Technical Challenges & Costs Are Growing

Our visibility always ~10 yrs – need broad exploration

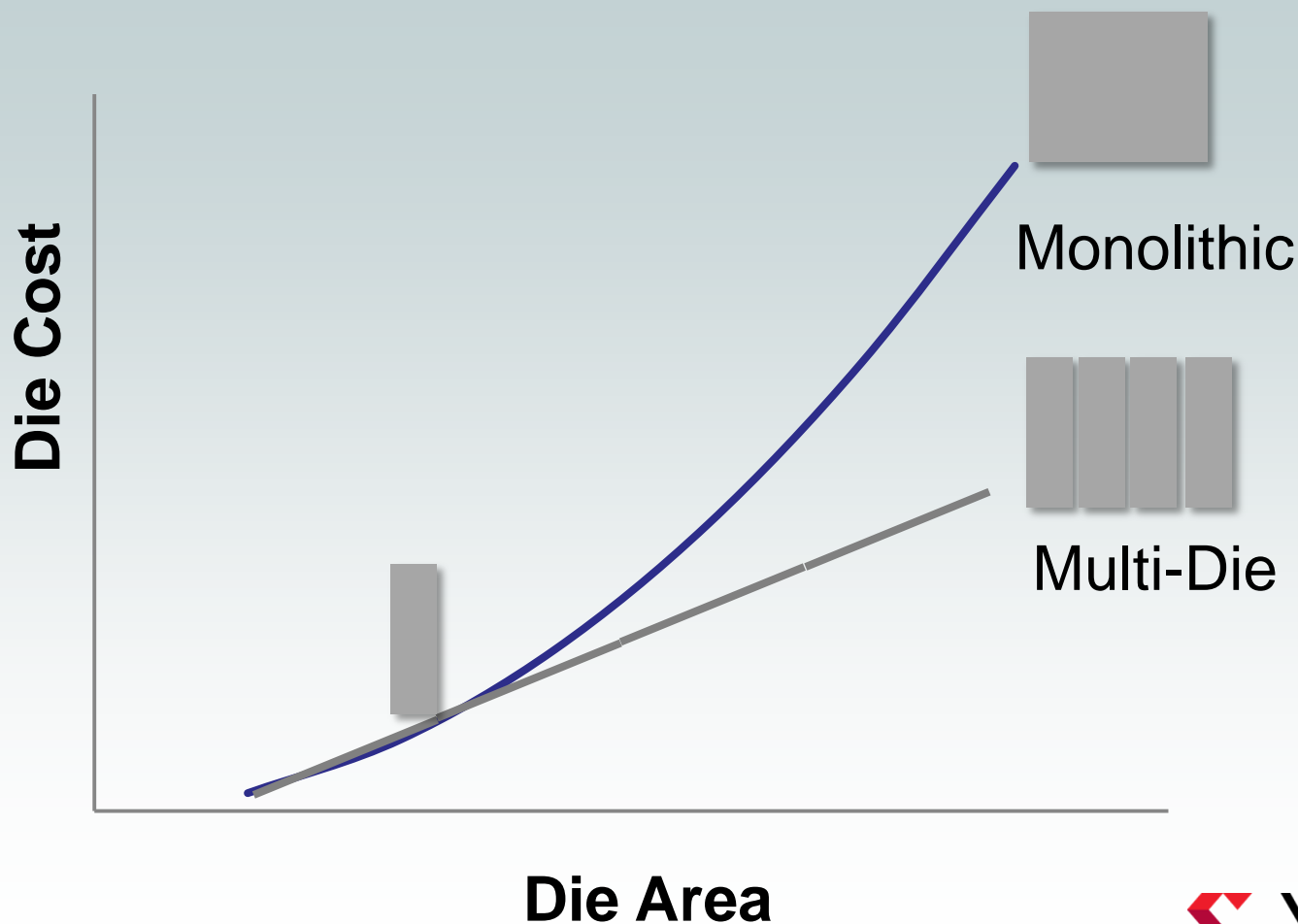


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# 3DIC Extends Moore's Law

## Cost Comparison: Monolithic vs. Multi-Die

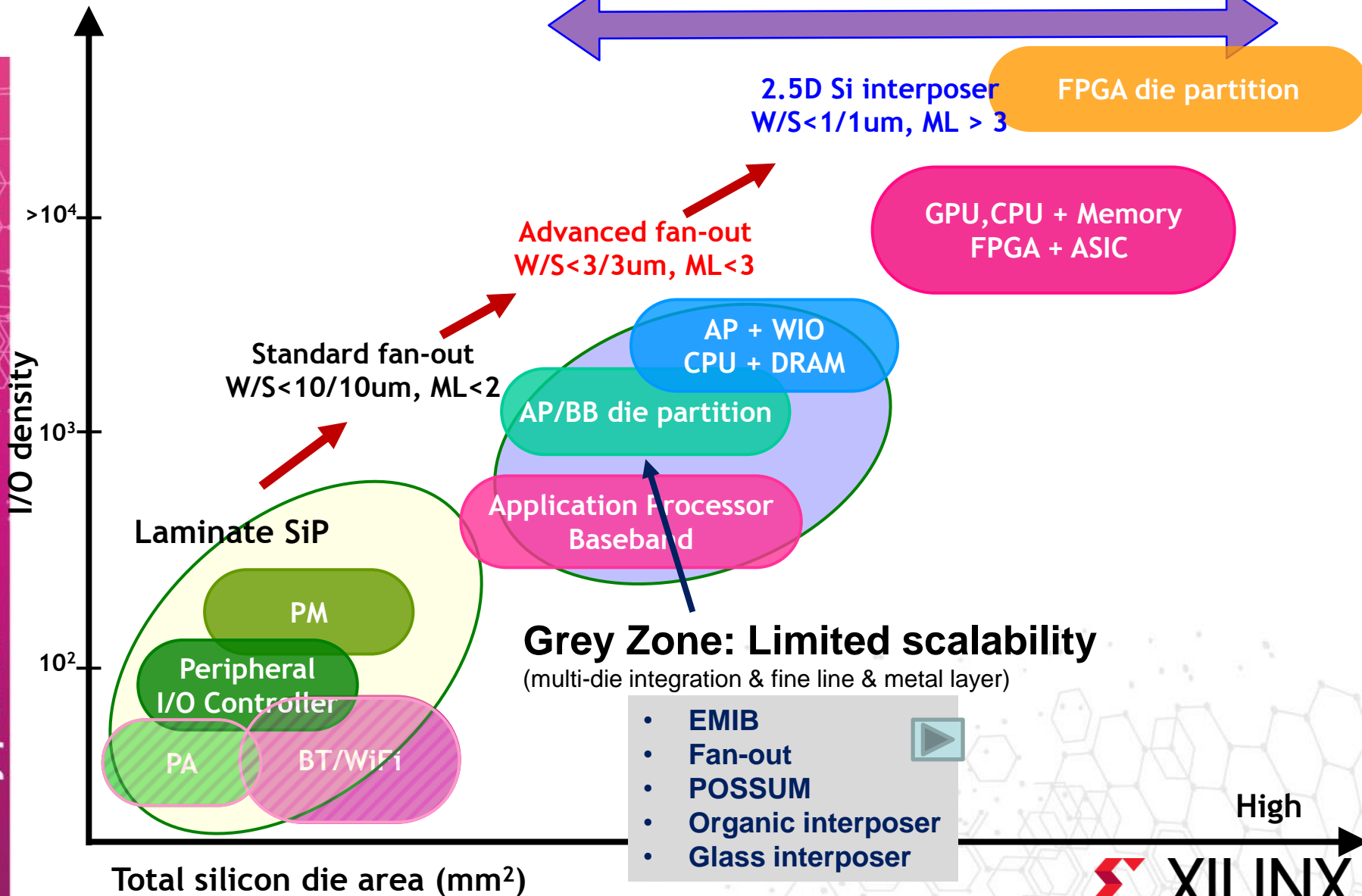
*"Moore's Law is Really About Economics"* – Gordon Moore





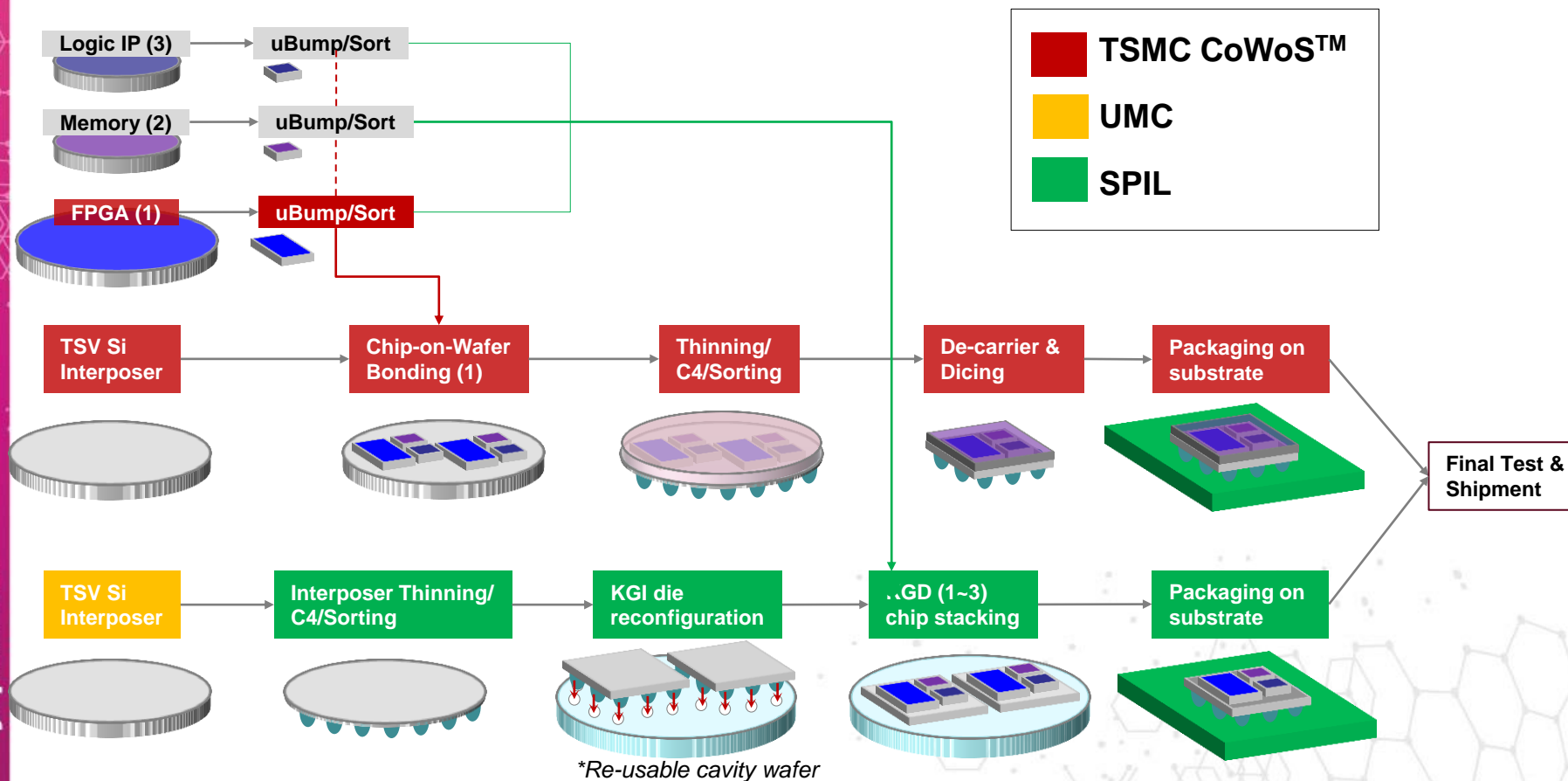
# 2.5D Technology Platform

Xilinx focus is lower CoO with 65nm DR



# Supply Chain

- TSMC CoWoS in production
- UMC/SPIL technology is ready





# Xilinx 28nm 3D IC – Huge Leap in Innovation

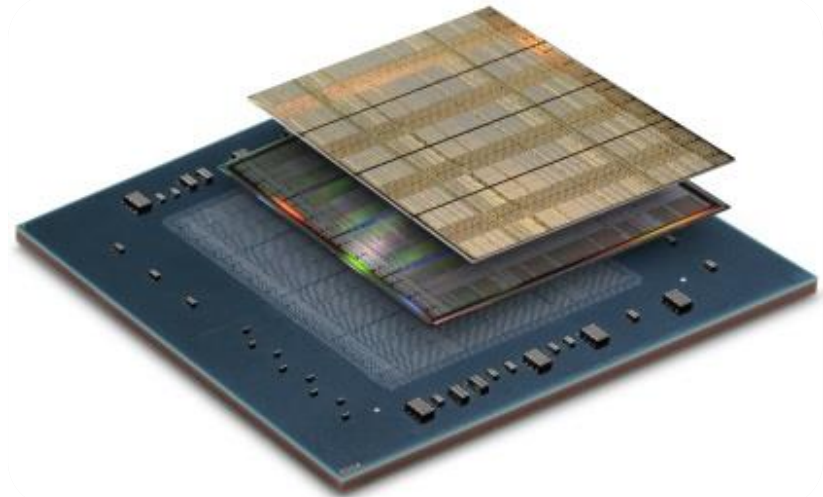


## Earth

Area: ~500 Million km<sup>2</sup>

Population: ~6.8 Billion People

Oceans: 5



## Virtex-7 2000T

Interposer Area: ~775 mm<sup>2</sup>

Population: ~6.8 Billion Transistors

Chips: 5

- 136 Patents Awarded Worldwide
- 226 Pending Applications Worldwide

# 3D IC Technology Development

# 3D IC Anatomy & Assembly Flow

## Passive Silicon Interposer (65nm)

➤ 4 Metal Layers Connecting Micro-Bumps & TSVs

### Micro-Bumps

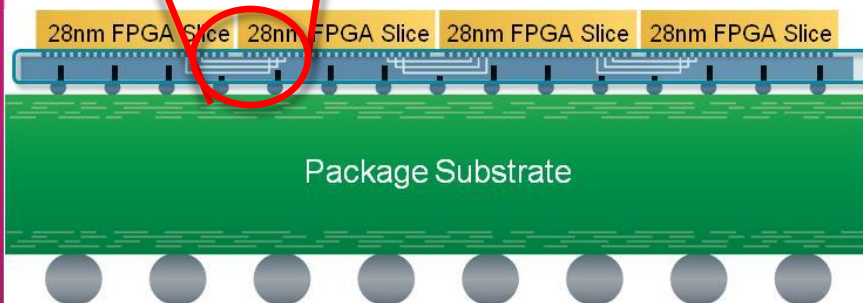
➤ Power / Ground / IOs / Routing

### C4 Bumps

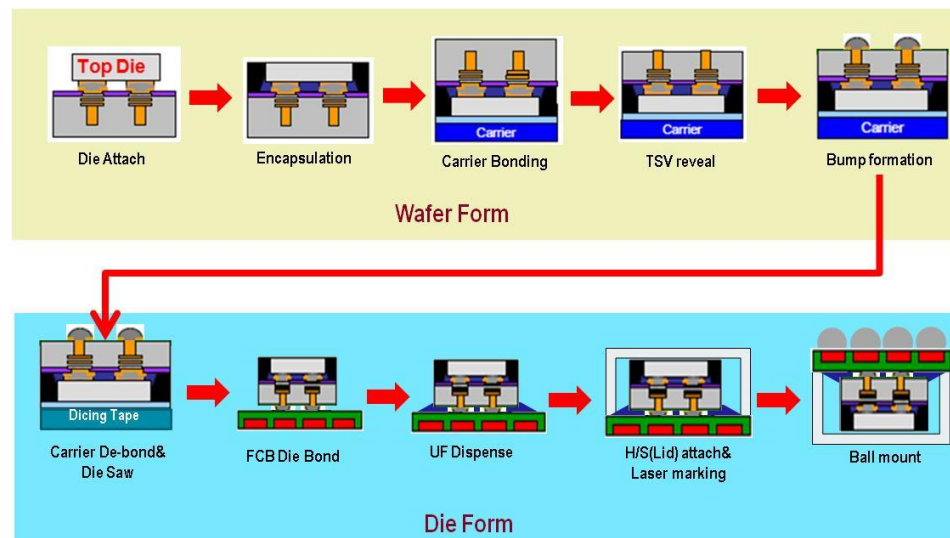
➤ Connects Silicon to Package

### Through-Silicon Via (TSVs)

➤ Connects Power / Ground / IOs to C4 Bumps



## Primary Chip on Wafer Assembly Steps



- > 150,000 Micro-bumps
- > 10,000 TSVs
- > 10,000 C4 Bumps
- > 90 Processing Steps in 3D IC Flow (From Bump to Completed Package)

*Achieved Good Yield & Quality*



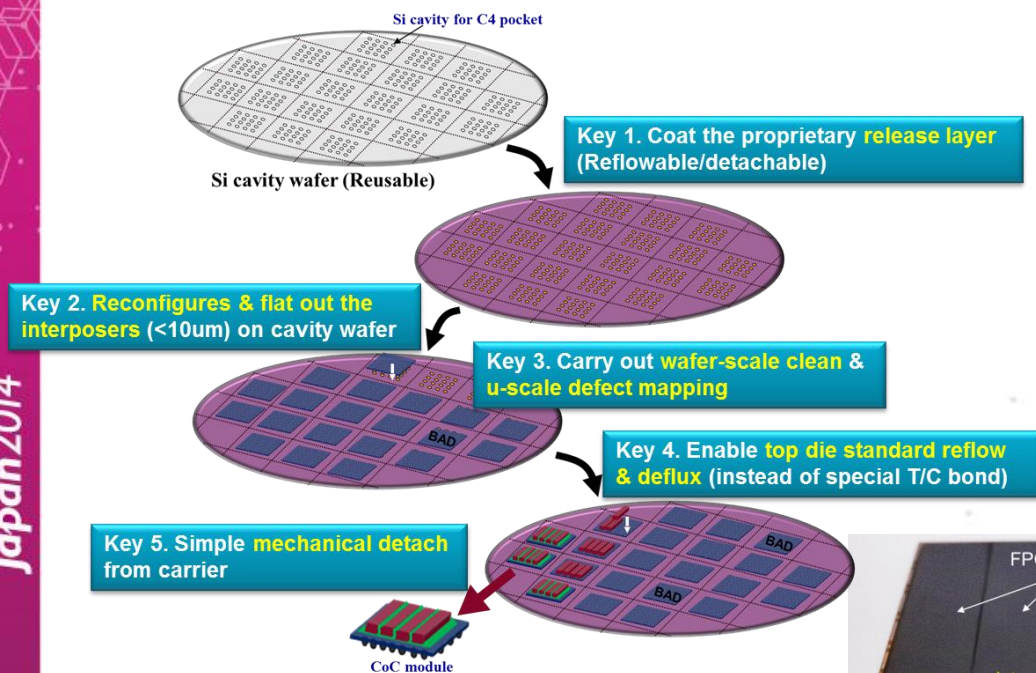
# Critical Challenge: Warpage Control

## ➤ CoWoS Technology

- Top dies are attached to full-thickness interposer wafers thus getting around the thin interposer warpage and poor micro-bump joining problem

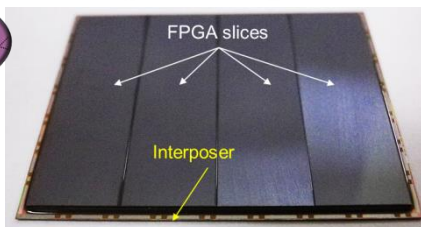
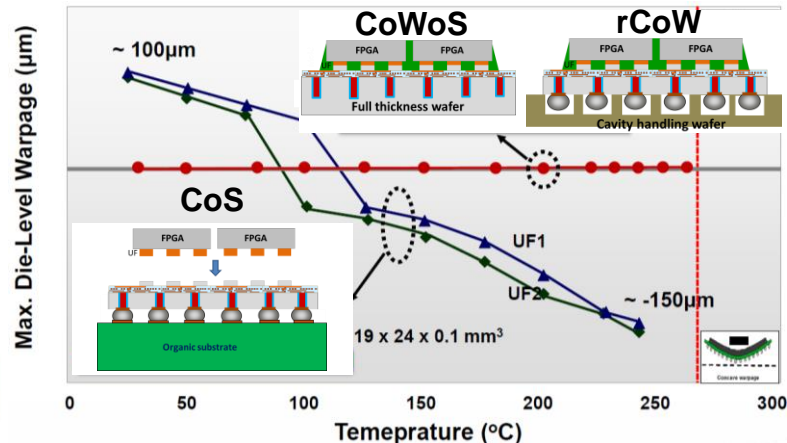
## ➤ Reconfigurable CoW (rCoW) Technology

- Xilinx patent issued worldwide (US/TWN/CN/EU/IND/JPN/KR)
- Release layer approach that withstands reflow & maintains low warpage



## Warpage control

Keep warpage below <10um over entire temp range



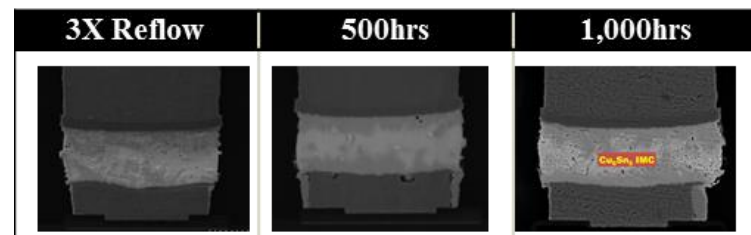
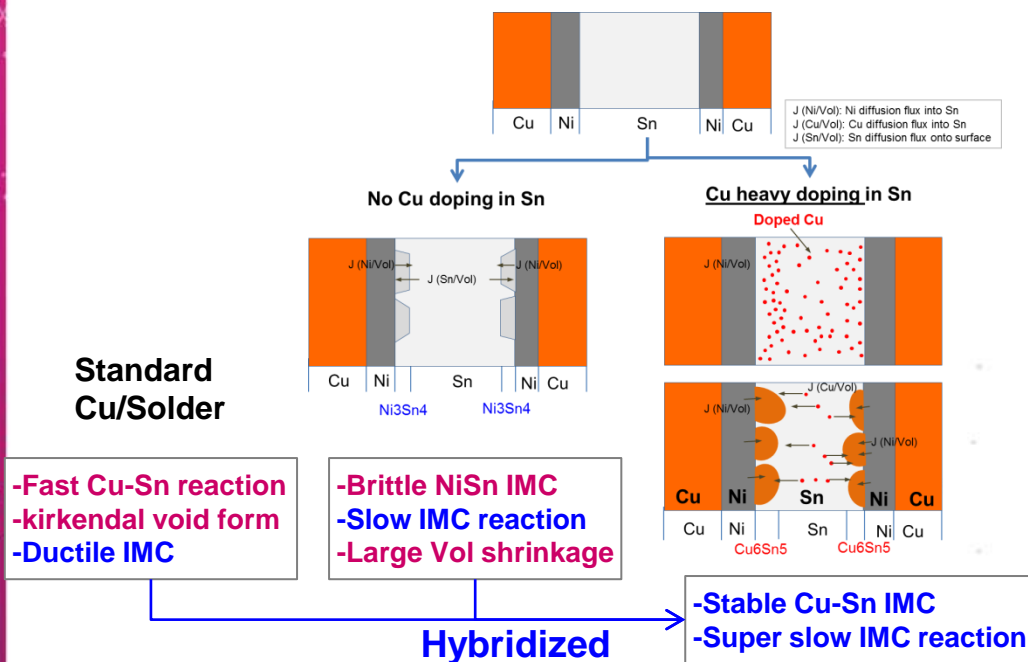


# HTS Aging Reliability Issue

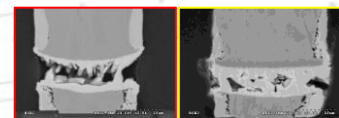
- **Voiding or crack in micro-joint during long term stress (HTS in particular)**
  - Due to limited Sn source and its dual consumption rate from top and bottom pad
- **Resolution : Heavy Cu doping into LF solder cap (with Ni barrier layer)**
  - Take advantages of ductile IMC (Cu-Sn) and slower IMC reaction (Ni with Cu-Sn IMC)
  - Passed 3X reflow + 150°C aging condition for > 1000 hrs

## Diffusion flux model of inter-diffusion

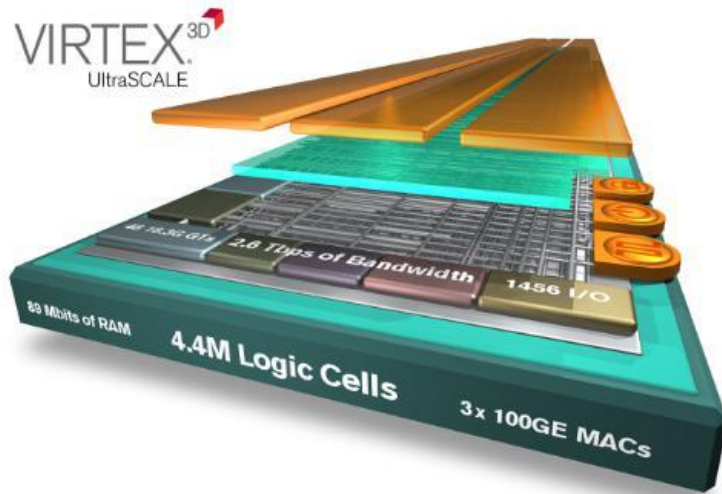
## HTS aging performance



\*Reference images  
(from no-doping u-bump)

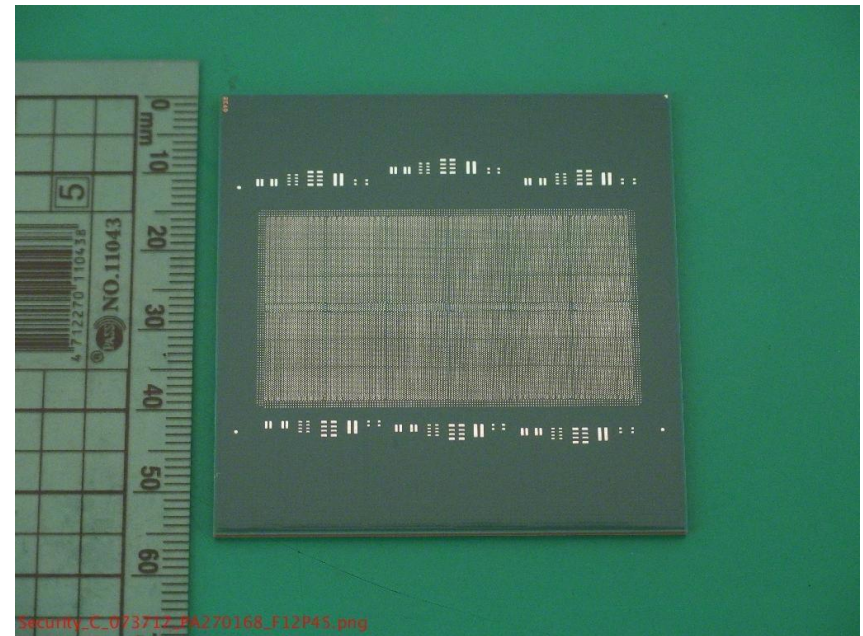
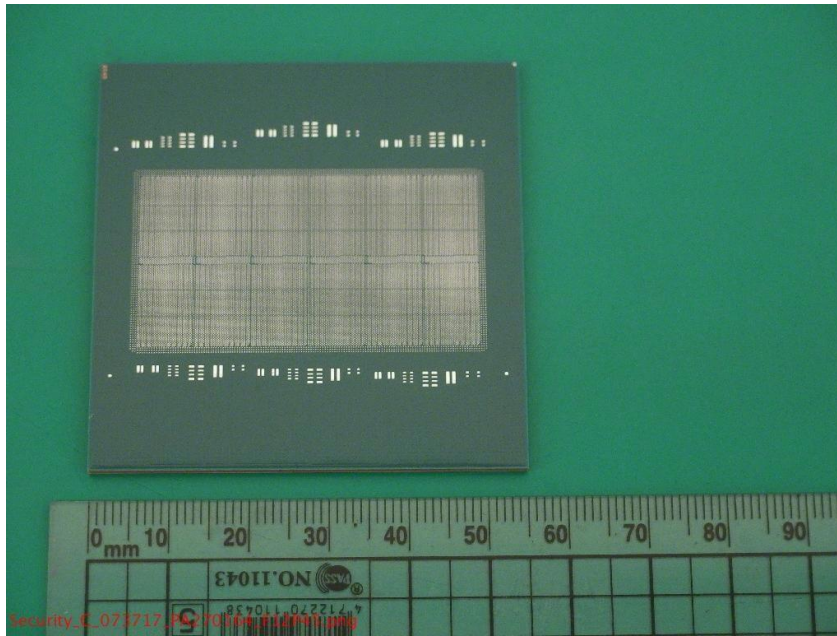


# Leadership Continues at 20/16nm - UltraSCALE



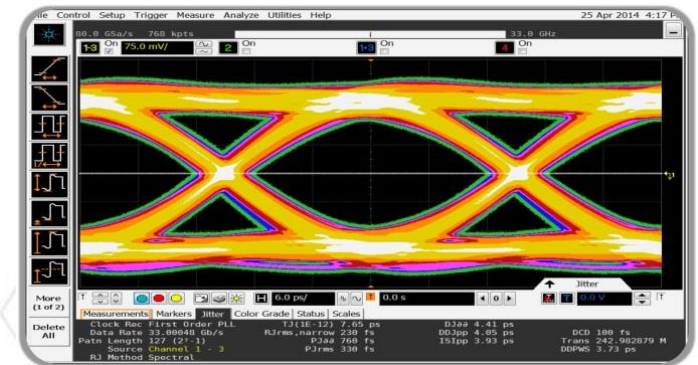
- 4.4M Logic Cells in 20nm
- 14B transistors
- 600,000 micro-bumps
- 55mm package, 2892 pins

# Leadership Continues at 20/16nm - UltraSCALE



## 32G TX Eye

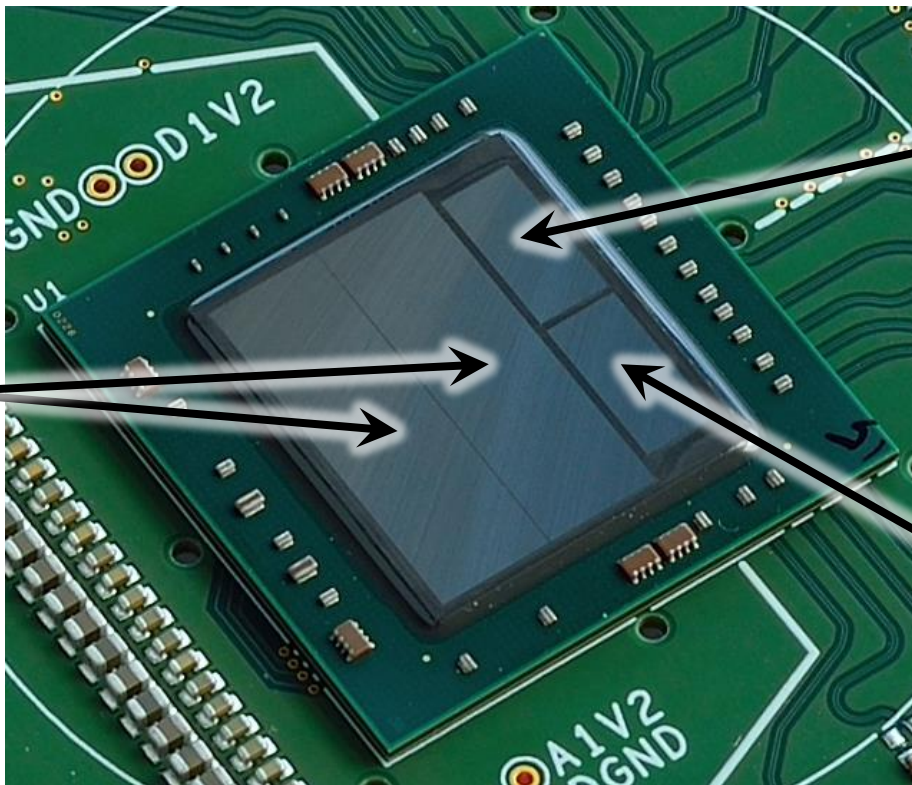
- 2.0 dB insertion loss at Nyquist Frequency
- Low loss substrate and design
- 23,000 C4 bumps





# Demo High Performance Mixed Signal Integration

2 x Virtex-7  
350T slices



Array of 16 DACs  
16-bit – 1.6GS/s

Array of 16 ADCs  
13-bit – 125MS/s

➤ Industry first 3D FPGA/Mixed Signal integration (ISSCC 2014)

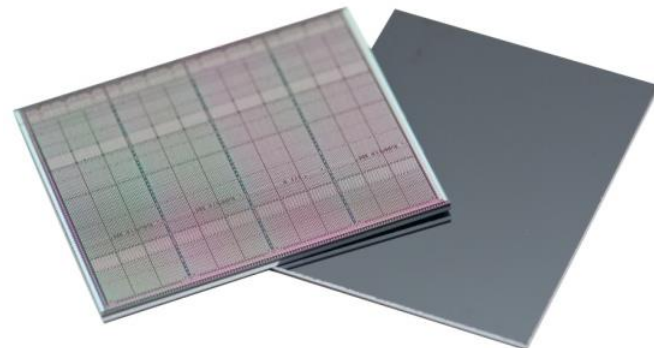


# Si-Less/TSV-less Interconnect Tech (SLIT) Builds on Interposer

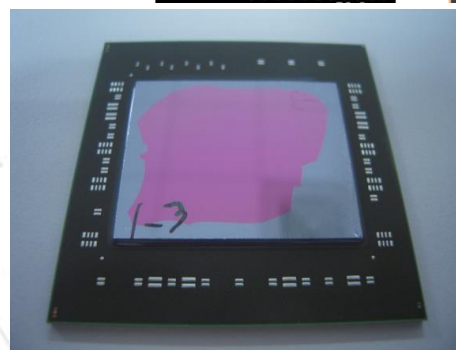
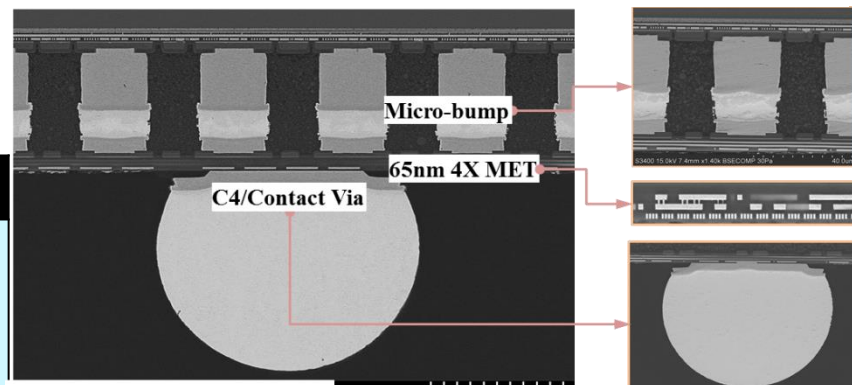
## ➤ Key Benefits

### ❖ Lower cost of ownership

- No HR-Si substrate used & less process modules (No TSV module/TBDB/TSV revealing)



	SLIT (Under development)	
Structure		
High-R Si substrate		×
65nm 4X Metal		○
TSV Creation		×
Micro-bumping		○
Temporary carrier		⊙
Thinning		○
TSV Revealing		×



Xilinx, SPIL (iMAPS 2014)



# 3D IC Technology Landscape

	Chip level	Device level	W2W C2W level
Players	<b>Samsung</b> DRAM / <b>Hynix</b> NAND & DRAM / <b>IBM</b> / <b>Micron</b> / <b>Elpida</b> / <b>Qualcomm</b> / <b>Nokia</b>	<b>Samsung</b> Vertical-Gate NAND / <b>Besang</b> / Monolithic 3D IC / Stanford	<b>SONY</b> (Stacked CIS) / <b>Tezzaron</b> / Ziptronix/ MIT Lincon Lab
TSV size	5~10um	0.5~2um contact through oxide	2~5um in diameter
TSV pitch	30~50um	1~4um (not limited)	5~10um
TSV count	1k~5k	Not limited	Not limited

Key features

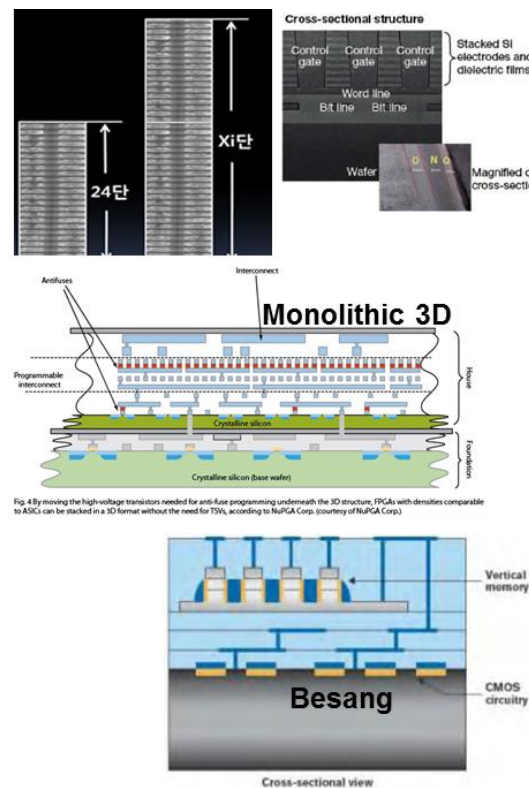
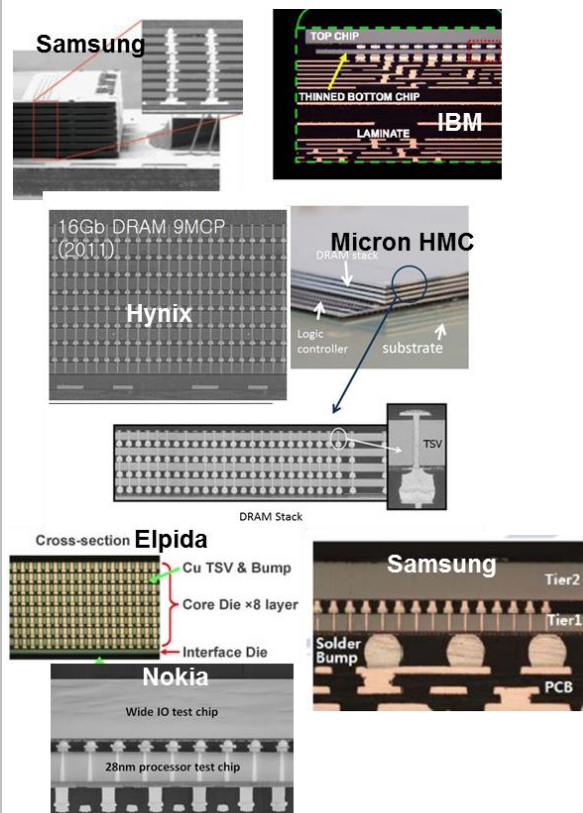
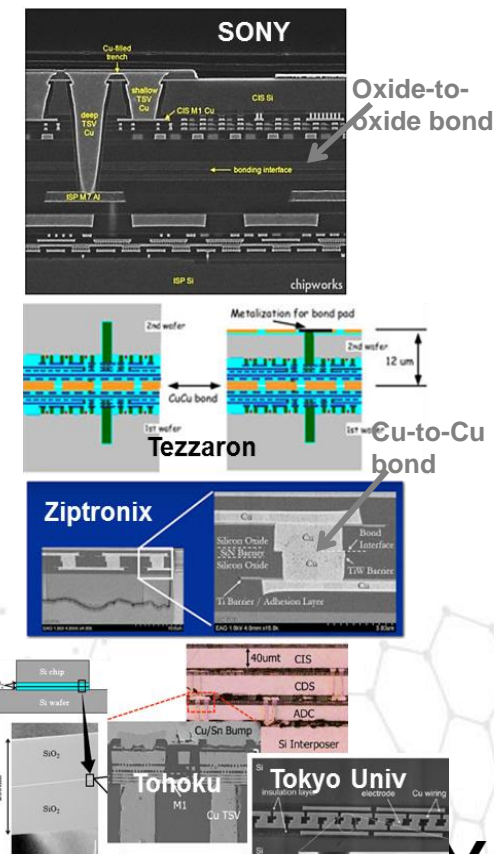


Fig. 4 By moving the high-voltage transistors needed for anti-fuse programming underneath the 3D structure, FPGAs with densities comparable to ASICs can be stacked in a 3D format without the need for TSVs, according to NuPGA Corp. (courtesy of NuPGA Corp.)



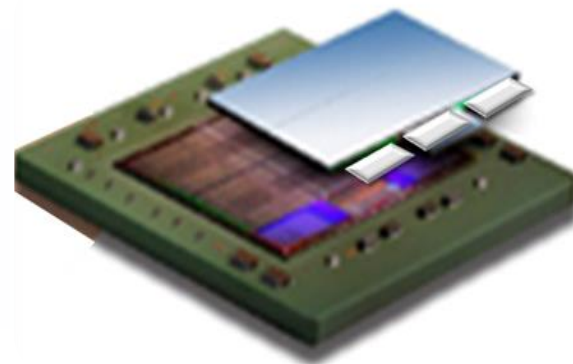
# Summary

- Economic and technology forces are aligned to enable 2.5D/3D stacking

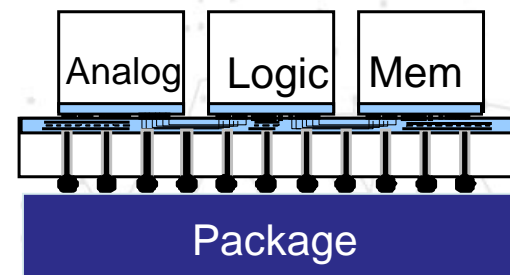
**STACKONOMICS**



- TSV and 3D stacking already deployed in Smartphones, High end FPGAs & Servers



- The “end game” will see three distinct technologies: Logic, Memory, Analog



# Acknowledgements

- Xilinx

- R&D, Reliability, NPI, Operations and Marketing Teams

- Partners

- TSMC R&D and Production Teams for FPGA, CoWoS
- UMC for Interposer
- SPIL R&D for MEOL and Advanced Packaging
- Fujitsu Interconnect Technology for High Speed Substrates





# Design Rule Comparison

Design Rules for Die to Die interconnection	MCM (Substrate )	EMIB	Silicon Interposer (65 nm BEOL)	WLFO / Organic Interposer
Minimum Bump pitch (um)	150 (C4)	150 (C4) 40 (u-bump) bridge	< 40 (u-bump)	40 um RDL pad pitch
Via size / pad size (um)	60 / 90	0.4 / 0.7	0.4 / 0.7	10/30
Minimum Line & Space (um)	15 / 15	0.4 / 0.4	0.4 / 0.4	3 / 3
Metal thickness (um)	10	1	1	2-5
Dielectric thickness (um)	30	1	1	< 5
# of die-to-die connections per layer + GND shield layer (2L)	100's	10,000's	10,000's	1000's
Minimum die to die spacing (um)	4000	Bridge ~ 2500	150	< 250
# of High density layers feasible	Not a limitation	Not a limitation	Not a limitation	1-3L layers
Die Sizes for assembly and # of assemblies	Not a concern	Size & # limitation?	Not a concern	Size limitation?

➤ **Xilinx pursuing Silicon Interposer for design rule density, BW and lower power – e.g. die partition**



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